



# Trymax

Trymax has established itself as a reputable supplier of advanced resist removal and plasma etching tools to the global semiconductor industry.

## Trymax NEO Products

- NEO200A: Compact single chamber tool, ideal for institutes and customers with lower volume requirements, for 200mm substrates
- NEO2000: Dual chamber high productivity platform for processing up to 200mm substrates
- NEO3000: Dual chamber high productivity platform with full bridge tool for processing 200/300 mm substrates
- NEO2400: Four chamber mass productivity platform for processing up to 200mm substrates
- NEO3400: Four chamber mass productivity platform for processing 200/300 mm substrates

Trymax has developed a range of different process modules for use on its various NEO platforms: high temperature microwave downstream module, RF based etching module and a low temperature dual source (RF+ Microwave) module.

With these different chamber configurations, the platforms can be used for a wide range of processes including

- Ashing of photoresist including high dose implanted and post etch material
- Controlled resist removal and descum processes
- Surface modification processes (eg. Smoothing, passivation, anodization)
- Removal of films: silicon nitride, silicon carbide, some thin metal films
- Dry film and organic polymer removal

Trymax has dedicated equipment assembly premises, a spare parts warehouse and a fully equipped customer demonstration facility at its Nijmegen headquarters. We have appointed a number of service representatives to support our global customer base. Currently we have fully staffed support offices in Singapore, Korea, Taiwan, China, Europe & USA.



**Leo Meijer**  
CEO  
E: leo.meijer@trymax-semiconductor.com  
T: +31 (0)6 536 250 45



**Ludo Vandenberg**  
Executive Vice President  
E: ludo.vandenberg@trymax-semiconductor.com  
T: +31 (0)6 297 378 99

Trymax 是全球半导体产业先进光刻胶去除和等离子刻蚀工具知名供应商。

## Trymax NEO 产品系列

- NEO200A: 紧凑型单腔设备 适于研发和小批量生产 用于200mm晶圆。
- NEO2000: 双腔高产平台 兼容200mm及以下晶圆加工。
- NEO3000: 双腔高产平台 带全转换工具，兼容200mm/300mm 晶圆加工。
- NEO3000: 四腔大批量生产平台 200mm及以下晶圆兼容。
- NEO3400: 四腔大批量生产平台 兼容200mm/300mm 晶圆加工。

Trymax 开发了不同的工艺模组系列，应用于多种NEO平台：高温微波下流型模组，基于射频的刻蚀模组，低温双源（射频+微波）模组等

通过这些不同的腔室配置，NEO产品可以用于以下广泛的制程：

- 光刻胶灰化，包括过量和蚀刻后残留
- 可控的光刻胶去除和去浮渣
- 表面改良工艺（平坦、钝化、极化）
- 去膜：如SiN SiC 某些金属薄膜
- 干膜和有机高分子膜去除

Trymax拥有专门的设备组装工厂、备品配件库和全套设备的客户展示中心，这些都位于其荷兰Nijmegen市的公司总部。我们委派了多位服务代表来支持我们的全球客户。目前我们在新加坡，韩国，台湾地区、中国、欧洲和美国有人员齐备的服务办公室。



## Contact

**TRYMAX SEMICONDUCTOR EQUIPMENT BV**  
Roggeweg 26B,  
6534 AJ Nijmegen,  
The Netherlands

T: +31 (0) 24 350 0809  
E: info@trymax-semiconductor.com

W: [www.trymax-semiconductor.com](http://www.trymax-semiconductor.com)